

Title (en)
CLEANING COMPOSITION, PAD, WIPE, IMPLEMENT, AND SYSTEM AND METHOD OF USE THEREOF

Title (de)
REINIGUNGSMITTELZUSAMMENSETZUNG, REINIGUNGSKISSEN UND -WISCHTUCH, REINIGUNGSGERÄT UND SYSTEM UND GEBRAUCH DES LETZTEN

Title (fr)
COMPOSITION DE NETTOYAGE, TAMPON, EPONGE, USTENSILE ET SYSTEME ET PROCEDE D'UTILISATION CORRESPONDANTS

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Abstract (en)
[origin: DE29924439U1] A cleaning implement for cleaning hard surfaces comprises a handle, a removable cleaning pad comprising absorbent layer and optionally cleaning element(s) such as perfumes and scrubbing layers etc. A cleaning implement comprises : (a) a handle; and (b) a removable cleaning pad comprising: (i) absorbent layer; and (ii) additional element(s) selected from: (aa) optionally, a liquid pervious scrubbing layer; (bb) optionally, an attachment layer; (cc) optionally, multiple planar surfaces; (dd) optionally, functional cuff(s); (ee) optionally, a density gradient throughout absorbent layer(s); (ff) optionally adhesive scrubbing strip(s) removably attached to the cleaning pad; and (gg) optionally, perfume carrier complex. Independent claims are also included for: (1) a hard surface cleaning composition comprising: (a) optionally, 0.001-0.5 wt.% of a composition of surfactant; (b) optionally, hydrophilic polymer; (c) optionally, organic solvent; (d) optionally, 0.01-1 wt.% of mono- or polycarboxylic acid; (e) optionally, 0.01-1 wt.% of odor control agent; (f) optionally, a source of peroxide; (g) optionally, 0.001-0.1 wt.% of a thickening polymer; (h) aqueous solvent system; (i) optionally, suds suppressor; (j) optionally, 0.005-0.2 wt.% of a perfume comprising: (i) optionally, 0.05-90 wt.% of perfume of volatile, hydrophilic perfume material; (ii) optionally, 0.2 wt.% of volatile, hydrophobic perfume material; (iii) optionally, less than 10 wt.% of residual, hydrophilic perfume material; and (iv) less than 10 wt.% of residual, hydrophobic perfume material; and (k) a detergent adjuvant; (2) a method of cleaning a hard surface comprising: (a) contacting the surface with a cleaning implement comprising a handle and a removable, dry cleaning substrate to remove dust and fine particulate matter from the surface; (b) contacting the surface with a hard surface cleaning composition to wet the surface; (c) contacting the wet surface with a cleaning implement comprising a handle and a removable cleaning pad to remove the hard surface cleaning composition from the surface; and (d) allowing the surface to dry without rinsing the surface with a separate rinse solution; (3) A method of cleaning hard surfaces comprising: (a) contacting the surface with a cleaning implement comprising a handle and a removable dry, cleaning substrate to remove dust and fine particulate matter from the surface; (b) contacting the surface with a cleaning implement comprising a handle and a removable, pre-moistened cleaning wipe to remove additional soil from the surface; and (c) allowing the surface to dry without rinsing the surface with a separate rinse solution; (4) a cleaning implement comprising: (a) a handle; (b) a support head pivotally attached to the handle; (c) a cleaning substrate removably attached to the support head, the substrate having an absorbent capacity of at least 5 g/g; and (d) a liquid delivery system for providing a cleaning liquid to a surface to be cleaned, the system being configured to spray at least 2 mls/sec of a cleaning liquid; and (5) a cleaning implement comprising: (a) a handle; (b) a support head pivotally attached to the handle; (c) a cleaning substrate removably attached to the support head, the substrate; and (d) a hand held liquid sprayer removably attached to the cleaning implement for dispensing liquid onto the surface to be cleaned.

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